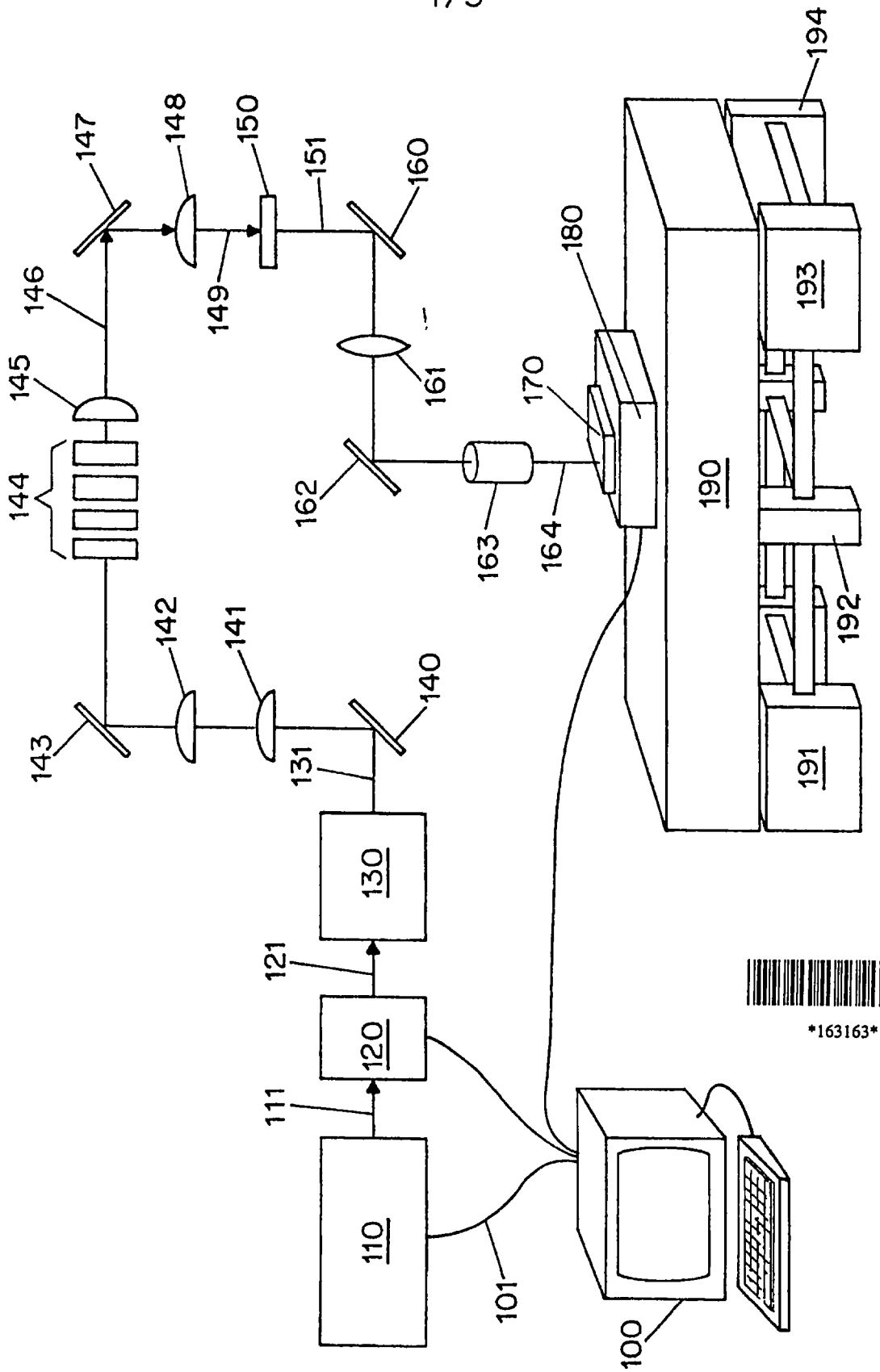

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FIG. 1

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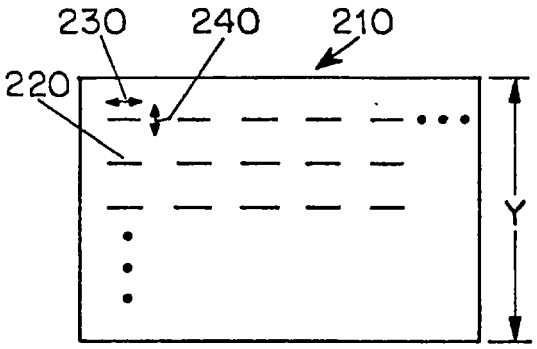


FIG. 2A

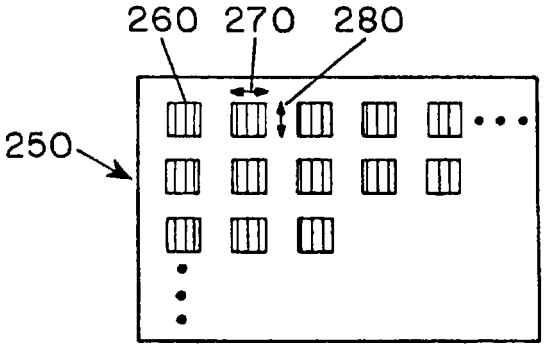


FIG. 2B

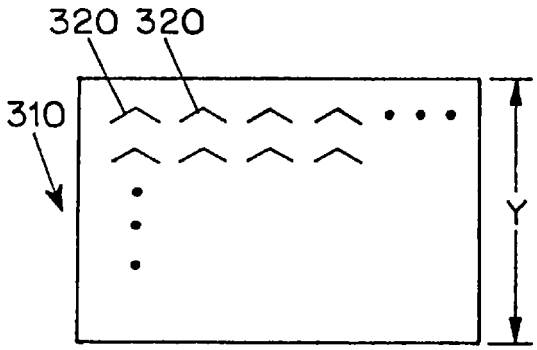


FIG. 3A

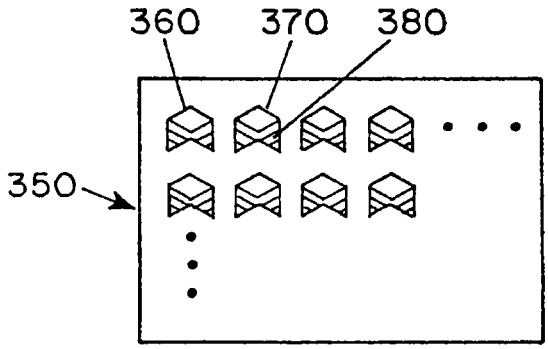


FIG. 3B

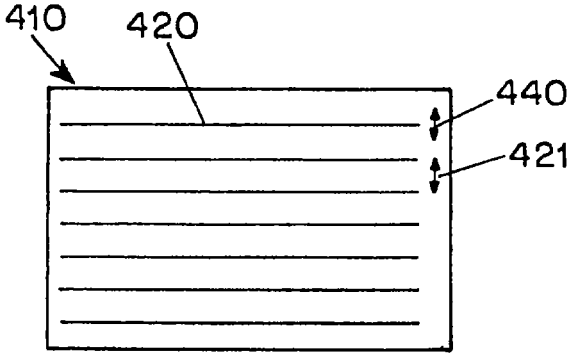


FIG. 4A

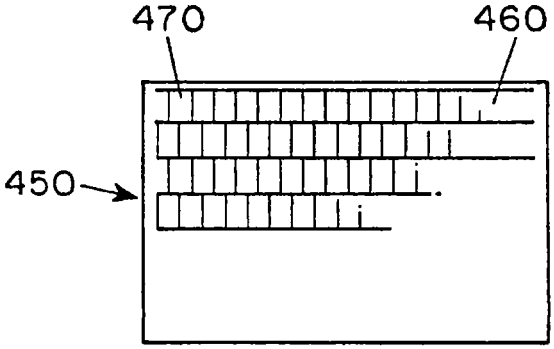


FIG. 4B

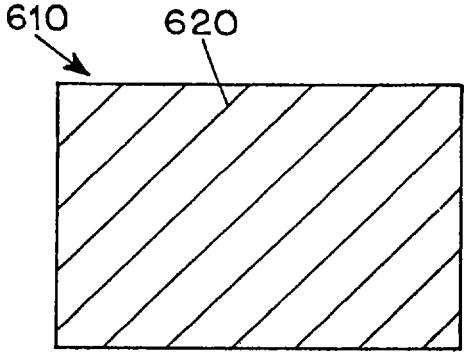


FIG. 6A

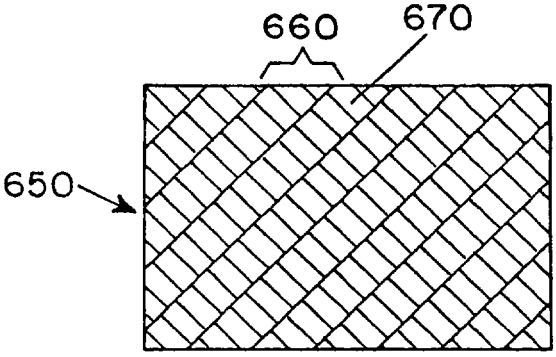


FIG. 6B

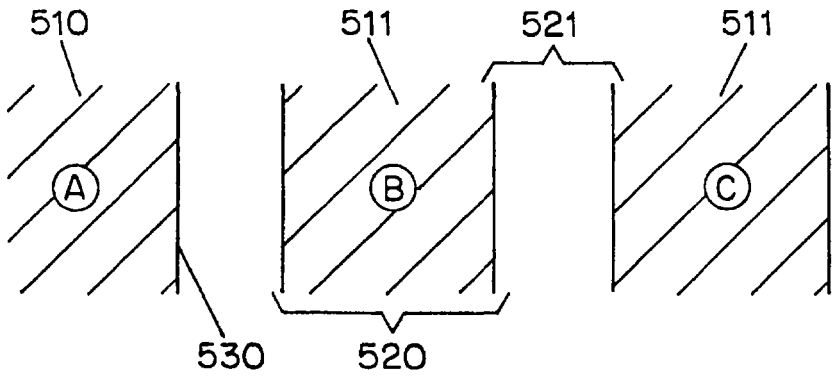


FIG. 5A

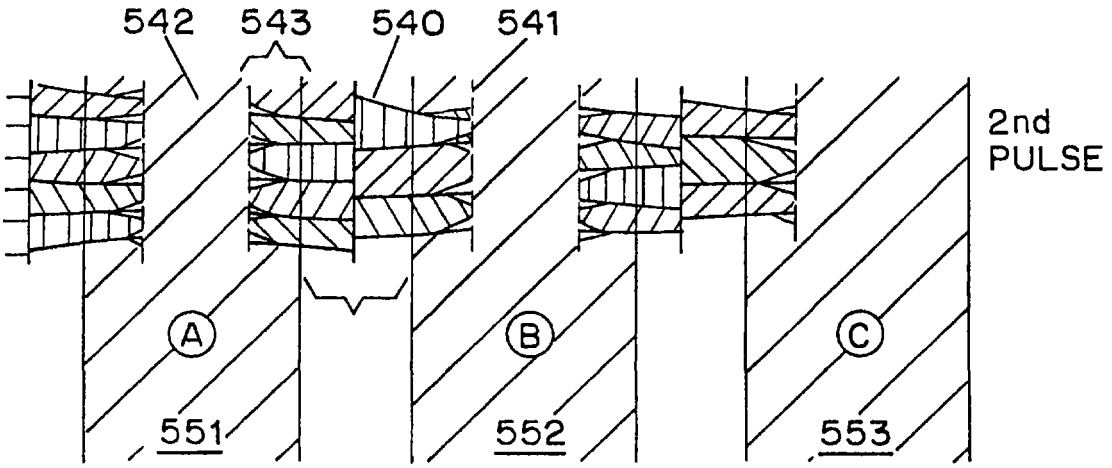


FIG. 5B

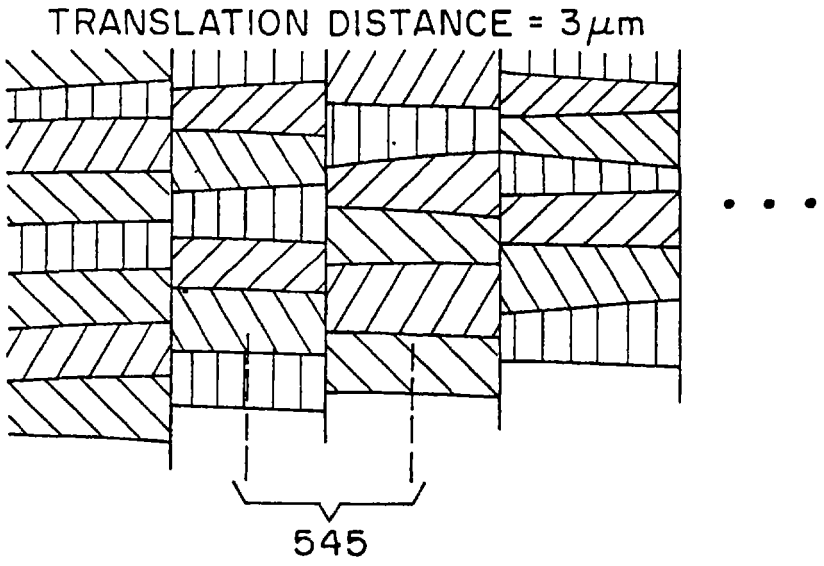


FIG. 5C

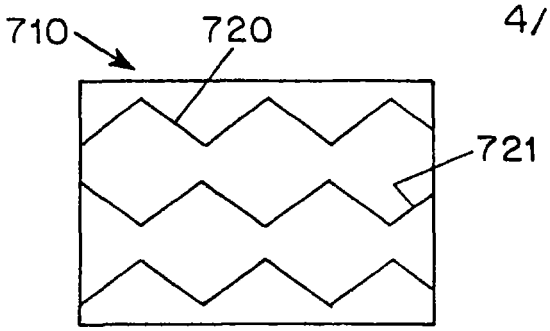


FIG. 7A

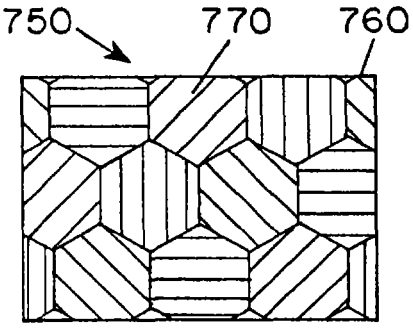


FIG. 7B

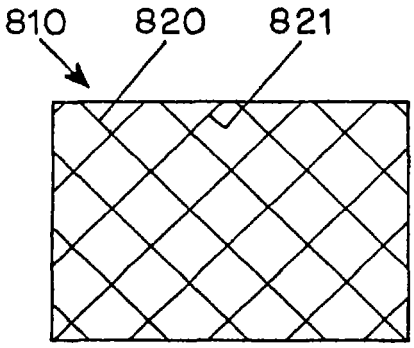


FIG. 8A

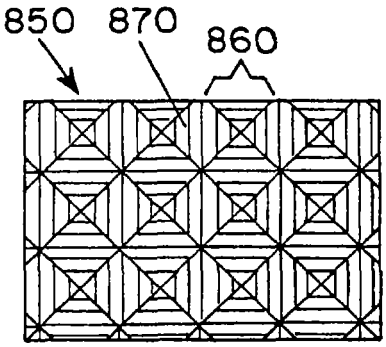


FIG. 8B

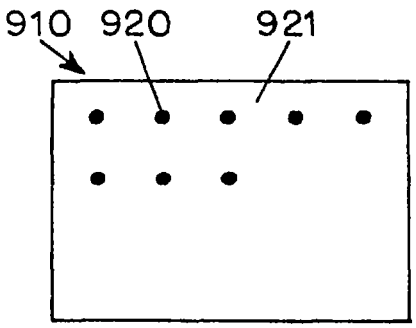


FIG. 9A

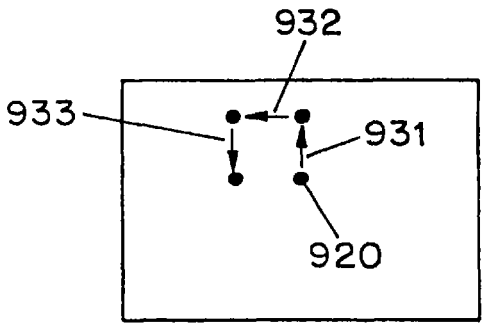


FIG. 9B

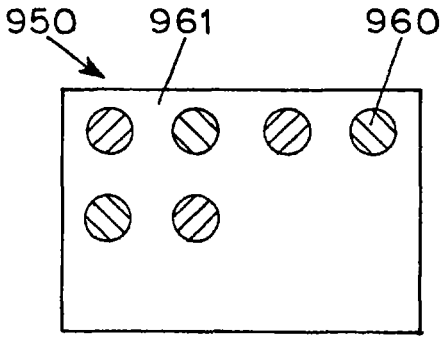


FIG. 9C

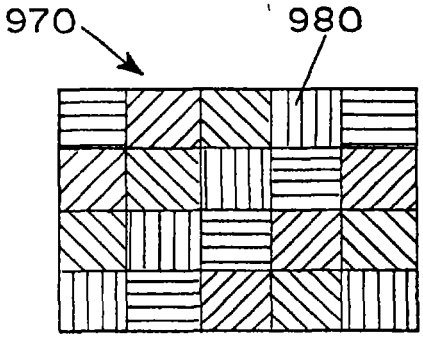


FIG. 9D

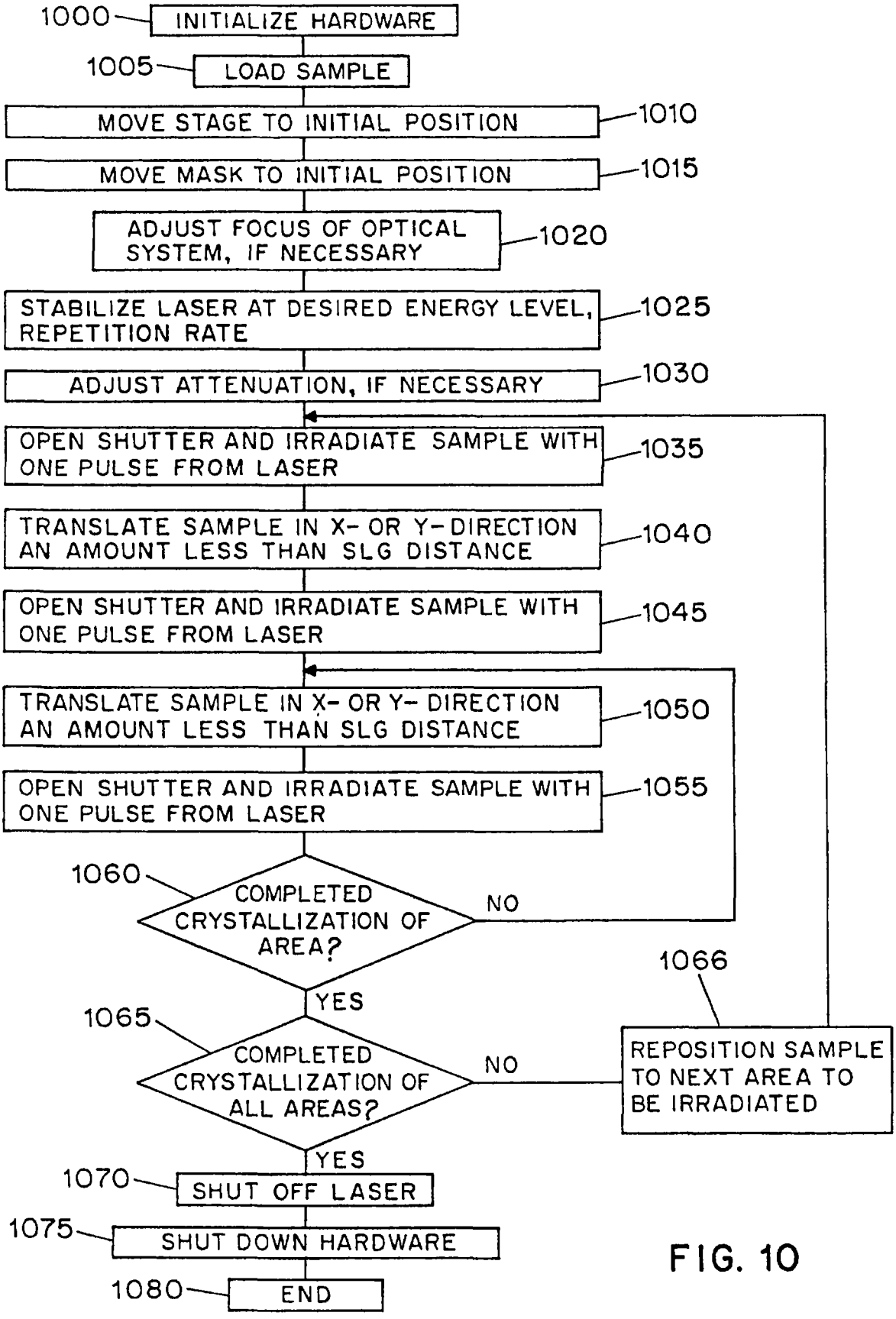

1000
INITIALIZE HARDWARE
1005
LOAD SAMPLE
MOVE STAGE TO INITIAL POSITION
1010
MOVE MASK TO INITIAL POSITION
1015
ADJUST FOCUS OF OPTICAL SYSTEM, IF NECESSARY
1020
STABILIZE LASER AT DESIRED ENERGY LEVEL, REPETITION RATE
1025
ADJUST ATTENUATION, IF NECESSARY
1030
OPEN SHUTTER AND IRRADIATE SAMPLE WITH ONE PULSE FROM LASER
1035
TRANSLATE SAMPLE IN X- OR Y-DIRECTION AN AMOUNT LESS THAN SLG DISTANCE
1040
OPEN SHUTTER AND IRRADIATE SAMPLE WITH ONE PULSE FROM LASER
1045
TRANSLATE SAMPLE IN X- OR Y- DIRECTION AN AMOUNT LESS THAN SLG DISTANCE
1050
OPEN SHUTTER AND IRRADIATE SAMPLE WITH ONE PULSE FROM LASER
1055
1060
COMPLETED CRYSTALLIZATION OF AREA?
NO
YES
1066
REPOSITION SAMPLE TO NEXT AREA TO BE IRRADIATED
1065
COMPLETED CRYSTALLIZATION OF ALL AREAS?
NO
YES
1070
SHUT OFF LASER
1075
SHUT DOWN HARDWARE
1080
END

FIG. 10